(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau

(43) International Publication Date
19 May 2011 (19.05.2011)

PCT

(10) International Publication Number
WO 2011/060443 A2

(51) International Patent Classification: Not classified

(21) International Application Number:
PCT/US2010/056894

(22) International Filing Date:
16 November 2010 (16.11.2010)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
61/261,715 16 November 2009 (16.11.2009) US
12/946,149 15 November 2010 (15.11.2010) US

(71) Applicant *(for all designated States except US)*: **XYRATEX TECHNOLOGY LTD.** [GB/GB]; Langstone Road, Havant, Hants PO9 1SA (GB).

(72) Inventor; and

(75) Inventor/Applicant *(for US only)*: **MILLER, Kenneth, C.** [US/US]; 46831 Lakeview Boulevard, Fremont, CA 94538 (US).

(74) Agent: **GENCARELLA, Michael, L.**; Martine Penilla & Gencarella, LLP, 710 Lakeway Drive, Suite 200, Sunnyvale, CA 94085 (US).

(81) Designated States *(unless otherwise indicated, for every kind of national protection available)*: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States *(unless otherwise indicated, for every kind of regional protection available)*: ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU,

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(54) Title: LAMINAR FLOW TANK

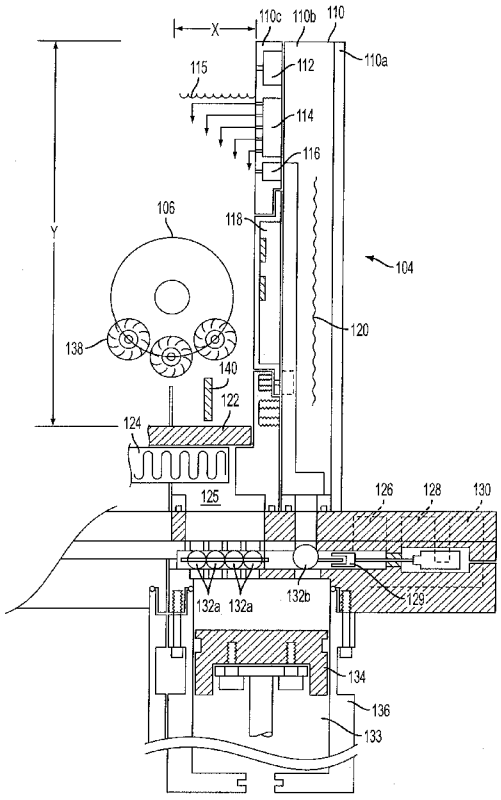


FIG. 2

(57) Abstract: A cleaning apparatus is provided. The cleaning apparatus includes a tank defined by sidewalls extending from a base. A plurality of fluid outlets defined within an upper portion of opposing sidewalls and are arranged as an array extending across a length and depth of the upper portion. The plurality of fluid outlets are configured to provide horizontally aligned fluid streams into an interior of the tank. The horizontally aligned fluid streams arranged such that an uppermost stream proceeds to an inner mid region of the tank and each successively lower stream proceeds closer to a sidewall from which the successively lower stream emanates, laminarly changing the direction of each of the horizontally aligned fluid streams to vertically aligned fluid streams toward a bottom of the tank. A support nest is disposed in a lower portion of the tank. A recirculation pump is disposed below the base of the tank. A method of cleaning a substrate is also provided.

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LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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